

Notice of References Cited	Application/Control No. 10/530,848		Applicant(s)/Patent Under Reexamination ABERLE ET AL.	
	Examiner JULIA SLUTSKER		Art Unit 2891	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2002/0052096 A1	05-2002	Zhang et al.	438/487
*	B	US-6,620,743 B2	09-2003	Pagliari et al.	438/787
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Aberle et al. "Formation of large-grained uniform poly-Si films on glass at low temperature", Journ Crystl.Growth, 226, (2001), pp.209-214
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.